

## Refine Search

### Search Results -

Terms	Documents
L16 and fluoride	26

**Database:**

US Pre-Grant Publication Full-Text Database  
 US Patents Full-Text Database  
 US OCR Full-Text Database  
 EPO Abstracts Database  
 JPO Abstracts Database  
 Derwent World Patents Index  
 IBM Technical Disclosure Bulletins

**Search:**

L17

Refine Search

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### Search History

DATE: Wednesday, April 05, 2006    [Printable Copy](#)    [Create Case](#)

<u>Set</u> <u>Name</u>	<u>Query</u>	<u>Hit</u> <u>Count</u>	<u>Set</u> <u>Name</u> result set
<i>DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>			
<u>L17</u>	L16 and fluoride	26	<u>L17</u>
<u>L16</u>	(2,4,7,9-tetramethyl-5-decyne-4,7-diol or tetramethyldecynediol or tetramethyl decyne diol or tetramethyl decynediol or tetra methyldecyne diol or tetra methyl decyne diol) and (abrasive or polishing (particle or particulate or grit or grain))	58	<u>L16</u>
<i>DB=PGPB,USPT; PLUR=YES; OP=ADJ</i>			
<u>L15</u>	L14 and fluoride	13	<u>L15</u>
<u>L14</u>	(junaid near2 siddiqui).in. and (abrasive or polishing)	16	<u>L14</u>
<u>L13</u>	L11 and L8	0	<u>L13</u>
<u>L12</u>	L11 and L7	0	<u>L12</u>
<u>L11</u>	L9 or L10	7	<u>L11</u>
<u>L10</u>	6309560.pn. or 5993686.pn.	2	<u>L10</u>
<u>L9</u>	US-5527423-\$.DID. OR US-6063306-\$.DID. OR US-630956B-\$.DID. OR	5	<u>L9</u>

US-5340370-\$.DID. OR US-5516346-\$.DID. OR US-5836806-\$.DID.

*DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ*

L8 (abrasive or polishing adj (particle or particulate or grit or grain)) and (surfynol adj 104 or surfynolL104 or surfinol adj 104 or surfinoL104) and fluoride 24 L8

L7 (abrasive or polishing adj (particle or particulate or grit or grain)) and (alkyne near10 hydroxyl or tetramethyl adj2 decyn adj4 diol or acetylenic adj alcohol or acetylenic adj glycol or Surfynol) and fluoride 95 L7

*DB=PGPB,USPT; PLUR=YES; OP=ADJ*

L6 L5 not l4 18 L6

L5 (polishing or planarizing or planarization or cmp or polish).ti. and colloidal (silica or silicon) and ammonium fluoride and surfactant 28 L5

L4 l1 and (polishing or planarizing or planarization or cmp or polish).ti. and colloidal (silica or silicon) and fluoride and surfactant 10 L4

L3 l1 and (polishing or planarizing or planarization or cmp or polish).ti. and colloidal (silica or silicon) and ammonium fluoride and surfactant 10 L3

L2 l1 and (polishing or planarizing or planarization or cmp or polish).ti. 10 L2

L1 colloidal silica and ammonium fluoride and nonionic surfactant 150 L1

END OF SEARCH HISTORY